

Claims

1. A substrate processing device comprising:
 - a processing bath configured to store processing liquid, and to process a plurality of substrates disposed at predetermined intervals;
 - first and second discharge units provided in the processing bath, each including a flow path in which the processing liquid flows in a thickness direction of the plurality of substrates, a plurality of openings formed along the flow path, and leading end surface closing a leading end of the flow path; and
 - a supply path that is configured to supply the processing liquid to proximal ends of the first discharge unit and the second discharge unit, and includes a supply port,wherein a length from the supply port to the leading end surface of the second discharge unit is substantially equal to a length from the supply port to the leading end surface of the first discharge unit.
2. The substrate processing device according to claim 1, wherein the second discharge unit is provided coaxially with the first discharge unit.
3. The substrate processing device according to claim 2, wherein the leading end surface of the second discharge unit is provided integrally with the leading end surface of the first discharge unit.
4. The substrate processing device according to any one of claims 1 to 3, wherein a total area of the plurality of openings in the first and second discharge units falls within a range from 20% to 28% of a cross-sectional area of the first and second discharge units.